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# UNITED STATES PATENT. D'1

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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO
10/647,985	08/26/2003	Patricia Beauregard Smith	TI-33260	3087
23494	7590 12/29/2005		EXAMINER	
TEXAS INSTRUMENTS INCORPORATED OIPE			EL ARINI, ZEINAB	
POBOX 655 DALLAS, T	5474, M/S 3999 X 75265	( Teo	ART UNIT	PAPER NUMBER
<i>21122113</i> , 11	, , , , , , , , , , , , , , , , , ,	( JAN 1 7 2006 3)	1746	
		\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\	DATE MAILED: 12/29/200	5
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Please find below and/or attached an Office communication concerning this application or proceeding.

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-		Application No.	Applicant(s)			
Office Action Summary		10/647,985	SMITH ET AL.			
		Examiner	Art Unit			
		Zeinab E. EL-Arini	1746			
Period fo	The MAILING DATE of this communication app r Reply	pears on the cover sheet with t	he correspondence address			
WHIC - Exter after: - If NO - Failui Any r	CRTENED STATUTORY PERIOD FOR REPLEMENTS. HEVER IS LONGER, FROM THE MAILING DISSIONS of time may be available under the provisions of 37 CFR 1.1 SIX (6) MONTHS from the mailing date of this communication. Period for reply is specified above, the maximum statutory period to to reply within the set or extended period for reply will, by statute eply received by the Office later than three months after the mailing patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICAT 36(a). In no event, however, may a reply will apply and will expire SIX (6) MONTHS a. cause the application to become ABAND	TION. be timely filed from the mailing date of this communication. FONED (35 U.S.C. § 133).			
Status						
1) 🛛	Responsive to communication(s) filed on <u>17 October 2005</u> .					
• -	•					
3)	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is					
·	closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.					
Dispositi	on of Claims					
4)⊠ Claim(s) <u>1-15 and 17-20</u> is/are pending in the application.						
	4a) Of the above claim(s) is/are withdrawn from consideration.					
5)	5) Claim(s) is/are allowed.					
6)⊠	☑ Claim(s) <u>1-15 and 17-20</u> is/are rejected.					
•	Claim(s) is/are objected to.					
8)□	Claim(s) are subject to restriction and/	or election requirement.				
Applicati	on Papers					
9) The specification is objected to by the Examiner.						
10)☐ The drawing(s) filed on is/are: a)☐ accepted or b)☐ objected to by the Examiner.						
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).						
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).						
11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.						
Priority (	under 35 U.S.C. § 119					
<ul> <li>12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).</li> <li>a) All b) Some * c) None of:</li> <li>1. Certified copies of the priority documents have been received.</li> <li>2. Certified copies of the priority documents have been received in Application No</li> </ul>						
3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).						
* See the attached detailed Office action for a list of the certified copies not received.						
Attachmer	nt(s)					
1) 🔲 Notic	ce of References Cited (PTO-892)	4) Interview Sun				
3) 🔲 Infor	ce of Draftsperson's Patent Drawing Review (PTO-948) mation Disclosure Statement(s) (PTO-1449 or PTO/SB/06 er No(s)/Mail Date	T	Mail Date rmal Patent Application (PTO-152)			

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#### **DETAILED ACTION**

The amendment and remarks filed 10/17/05 have been acknowledged and entered.

### Claim Rejections - 35 USC § 112

The following is a quotation of the second paragraph of 35 U.S.C. 112:

The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.

Claim 8 is rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

In claim 8, line 1, "the low- pressure anneal" lacks antecedent basis.

1. The following is a quotation of the first paragraph of 35 U.S.C. 112:

The specification shall contain a written description of the invention, and of the manner and process of making and using it, in such full, clear, concise, and exact terms as to enable any person skilled in the art to which it pertains, or with which it is most nearly connected, to make and use the same and shall set forth the best mode contemplated by the inventor of carrying out his invention.

2. Claims 1-18 are rejected under 35 U.S.C. 112, first paragraph, as failing to comply with the written description requirement. The claim(s) contains subject matter which was not described in the specification in such a way as to reasonably convey to one skilled in the relevant art that the inventor(s), at the time the application was filed, had possession of the claimed invention. The specification, as originally filed, does not provide support for "non-plasma anneal" as is now claimed in claim 1.

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## **Double Patenting**

The nonstatutory double patenting rejection is based on a judicially created doctrine grounded in public policy (a policy reflected in the statute) so as to prevent the unjustified or improper timewise extension of the "right to exclude" granted by a patent and to prevent possible harassment by multiple assignees. See *In re Goodman*, 11 F.3d 1046, 29 USPQ2d 2010 (Fed. Cir. 1993); *In re Longi*, 759 F.2d 887, 225 USPQ 645 (Fed. Cir. 1985); *In re Van Ornum*, 686 F.2d 937, 214 USPQ 761 (CCPA 1982); *In re Vogel*, 422 F.2d 438, 164 USPQ 619 (CCPA 1970);and, *In re Thorington*, 418 F.2d 528, 163 USPQ 644 (CCPA 1969).

A timely filed terminal disclaimer in compliance with 37 CFR 1.321(c) may be used to overcome an actual or provisional rejection based on a nonstatutory double patenting ground provided the conflicting application or patent is shown to be commonly owned with this application. See 37 CFR 1.130(b).

Effective January 1, 1994, a registered attorney or agent of record may sign a terminal disclaimer. A terminal disclaimer signed by the assignee must fully comply with 37 CFR 3.73(b).

Claims 1-3, 5-6, 9, 12, 15, and 20 are provisionally rejected under the judicially created doctrine of obviousness-type double patenting as being unpatentable over claims 1, 7, 30-31, 51, and 52 of copending Application No. 09/975,639. Although the conflicting claims are not identical, they are not patentably distinct from each other because the process in both applications are functionally equivalent.

This is a <u>provisional</u> obviousness-type double patenting rejection because the conflicting claims have not in fact been patented.

This rejection stated in paper No.061005 has been withdrawn in view of applicants' amendment, but well be reapply if the new matter is deleted.

Claim Rejections - 35 USC § 102

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3. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

Claims 1, 9-13, and 15 are rejected under 35 U.S.C. 102(e) as being anticipated by Yau et al. (US 2003/0194877 A1).

Yau et al. disclose a method for processing workpiece comprising etching metal from workpieces, wet cleaning and annealing the workpiece. See the abstract, and the claims. Removing polymer residue is inherent in the Yau et al. process. The reference discloses the high temperature anneal and the temperature of performing the anneal as claimed. See paragraphs 21, 23, and 27. Since the Yau et al. reference does not use plasma anneal, therefore the process as taught by Yau et al. considered to include non-plasma annealing step as claimed. The patterning step is inherent in the Yau et al. process.

This rejection stated in paper No. 061005 is maintained.

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 4. Claims 1-3, 5-8, 17-18, and 20 are, rejected under 35 U.S.C. 102(b) as being anticipated by Smith et al. (US 2002/0058397 A1).

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- 5. Smith et al. disclose a method of cleaning a wafer comprising cleaning a polymer residue from surfaces of the patterned dielectric layer overlying the wafer using a wet clean solvent; and performing the annealing step as claimed.
- 6. The reference discloses the patterning step, the dielectric layer, the acid, the dry clean, the plasma, the low pressure anneal, the cleaning performed after the via-etch process, the copper and barrier deposition as claimed. See the abstract, Fig. 1, paragraphs 17-27, and the claims.
- 7. The annealing step, in Fig. 1, step 110, is not plasma annealing.
- 8. This rejection stated in paper No. 061005 is maintained.

## Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 4, 14 and 19 are rejected under 35 U.S.C. 103(a) as being unpatentable over Smith et al. '397 in combination with Kim et al. (US 2004/0060579 A1).

Smith et al. as discussed supra disclose all limitation with the exception of wet clean process using solvent comprises dimethyl acetamide, and the time as claimed.

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Kim et al. disclose a method of cleaning ceramic parts after etching by using a solution comprises organic solvent. The organic solvent comprises dimethyl acetamid (DMAC). See paragraphs 43, 75-76, It would have been obvious for one skilled in the art at the time applicants invented the claimed process to use the acid taught by Kim et al. in the Smith et al. 397 process to improve the swelling effect, and therefore improving the cleaning process. It would have been obvious for one skilled in the art to adjust the time to obtain optimum results.

#### Response to Arguments

9. Applicant's arguments filed 10/17/05 have been fully considered but they are not persuasive. Applicants' argument with respect to the obviousness type double patenting rejection is persuasive, therefore said rejection has been withdrawn, but will be reapply if the new matter is deleted. With respect to 102(e) and 102(b) rejections, applicants' argument is unpersuasive, because the references do not disclose plasma annealing. With respect to 103(a) rejection, said 103(a) rejection has been withdrawn.

#### Conclusion

10. Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within

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TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any

extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of

the advisory action. In no event, however, will the statutory period for reply expire later

than SIX MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Zeinab E. EL-Arini whose telephone number is (571) 272-1301. The examiner can normally be reached on Monday-Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Michael Barr can be reached on (571) 272-1414. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Zeinab E. EL-Arini Primary Examiner Art Unit 1746

ZEE

12/22/05